

Title (en)

DEVICE FOR THE TREATMENT OF A SUBSTRATE BY MEANS OF AT LEAST ONE PLASMA JET

Title (de)

VORRICHTUNG ZUR BEARBEITUNG EINES SUBSTRATES MITTELS MINDESTENS EINES PLASMA-JETS

Title (fr)

DISPOSITIF POUR TRAITER UN SUBSTRAT AU MOYEN D'AU MOINS UN JET DE PLASMA

Publication

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Application

EP 05753782 A 20050608

Priority

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Abstract (en)

[origin: WO2005125286A2] The invention relates to a device (10) for treating a substrate (11) with the aid of at least one plasma jet (13). Said device comprises a receptacle (15) through which a carrier gas flows along a certain direction of flow (x), a first electrode (17), and a second electrode (18). The inventive device is characterized in that the two electrodes (17, 18) are separated from each other by means of at least one dielectric barrier (15) while an alternating voltage is applied between the electrodes (17, 18) in order to create an atmospheric pressure glow discharge plasma. Furthermore, the first electrode (17) is axially (L) and radially (R) spaced apart from the second electrode (18) relative to the direction of flow (x) of the carrier gas.

IPC 8 full level

H05H 1/24 (2006.01); **H05H 1/44** (2006.01)

CPC (source: EP US)

H05H 1/2406 (2013.01 - EP US); **H05H 1/246** (2021.05 - EP); **H05H 1/44** (2013.01 - EP)

Citation (search report)

See references of WO 2005125286A2

Cited by

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